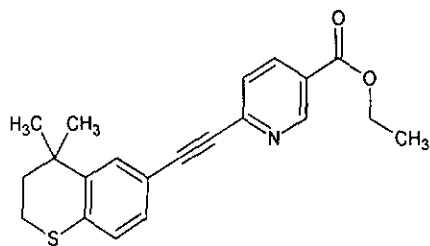
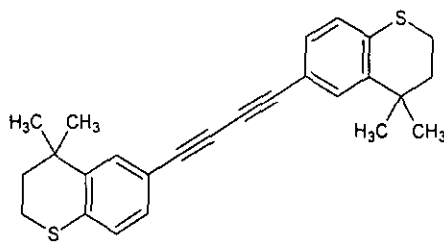


ABSTRACT

The present invention relates to a method of treating acne or psoriasis by topically administering Tazarotene, a compound of formula (I), substantially free of dimer impurity 4,4-dimethyl-6-[4-(4,4-dimethylthiochroman-6-yl)-buta-1,3-diynyl]-thiochroman, a compound of formula (II)



Formula I



Formula II

Dated 10 Dec 2013

(Signature).....

[Handwritten Signature]

(Sunil Ajmera
Company Secretary)

DILIP SHANTILAL SHANGHVI

MANAGING DIRECTOR

SUN PHARMACEUTICAL INDUSTRIES LTD

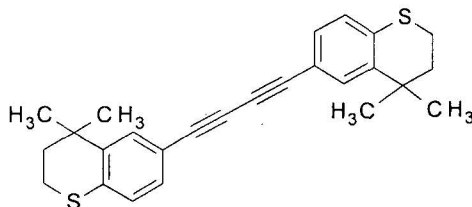
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Example 5: Composition for Tazarotene Gel (0.1% w/w)

Ingredients	Concentration (% w/w)
Disodium Edetate	0.05
Ascorbic acid	0.1
Carbomer homopolymer type B	1.25
Poloxamer 407	0.2
Tazarotene	0.1
Polyethylene Glycol 400	45
Hexylene Glycol	2
Butylated hydroxy toluene	0.05
Butylated hydroxy anisole	0.1
Polysorbate 40	0.2
Benzyl alcohol	1
Tromethamine	0.8
Purified water	q.s.

We Claim:

1. A method of treating acne or psoriasis by topically administering tazarotene substantially free of dimer impurity of Formula II.

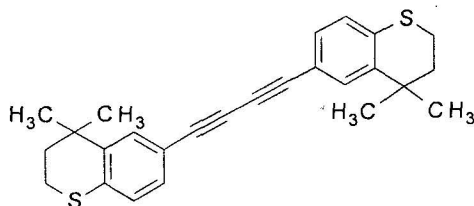


Formula II



2. The method of claim 1 wherein, the tazarotene contains less than 100 ppm of dimer impurity of Formula II.
3. The method of claim 1 wherein, the tazarotene contains less than 30 ppm of dimer impurity of Formula II.
4. The method of claim 1 wherein, the tazarotene contains less than 10 ppm of dimer impurity of Formula II.

5. The method of claim 1 wherein, the dimer impurity of Formula II in tazarotene is not detectable in said tazarotene.
6. A process for preparation of Tazarotene substantially free of dimer impurity of Formula II



Formula II

comprising:

- a. adding Tazarotene containing dimer impurity of Formula II to an organic solvent,
 - b. adding an acid and isolating the acid addition salt of tazarotene,
 - c. adding the tazarotene acid addition salt obtained in step b to an organic solvent and adding an aqueous solution of a base to obtain a biphasic mixture,
 - d. distilling the organic layer and treating the residue with a non-polar solvent,
 - e. optionally, repeating step a to d.
7. Tazarotene, obtained by the process of claim 6 containing less than 30 ppm of dimer impurity of Formula II.
 8. Tazarotene, obtained by the process of claim 6 containing less than 10 ppm of dimer impurity of Formula II.
 9. Tazarotene, obtained by the process of claim 6 wherein dimer impurity of Formula II is not detectable in said tazarotene.

Dated 12th Dec 2014

(Signature) *Ratnesh Shrivastava*

Dr. RATNESH SHRIVASTAVA

Vice President

Sun Pharmaceutical Industries Ltd